## This Page Is Inserted by IFW Operations and is not a part of the Official Record

## BEST AVAILABLE IMAGES

Defective images within this document are accurate representations of the original documents submitted by the applicant.

Defects in the images may include (but are not limited to):

- BLACK BORDERS
- TEXT CUT OFF AT TOP, BOTTOM OR SIDES
- FADED TEXT
- ILLEGIBLE TEXT
- SKEWED/SLANTED IMAGES
- COLORED PHOTOS
- BLACK OR VERY BLACK AND WHITE DARK PHOTOS
- GRAY SCALE DOCUMENTS

## IMAGES ARE BEST AVAILABLE COPY.

As rescanning documents will not correct images, please do not report the images to the Image Problem Mailbox.

handle wafer

W backgate

0.17

Si Substrate

handle wafer

LTO

W backgate gafe oxide Si Channel gafe oxide

Si Substrate

handle wafer

CFO

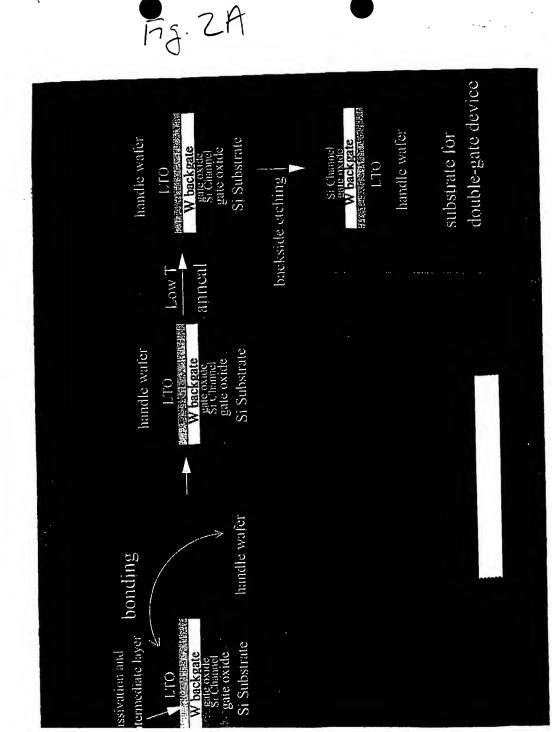
W backgate gate oxide Si Channel gate oxide

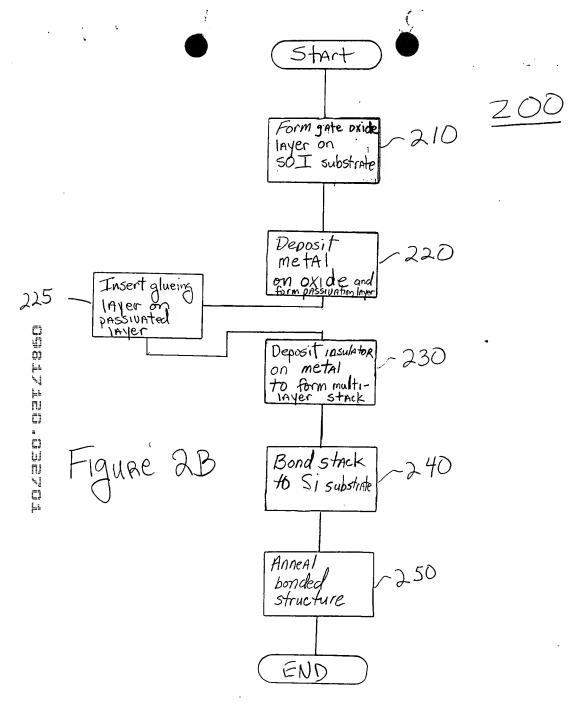
anneal

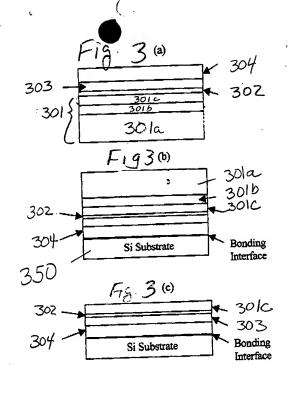
Si Substrate

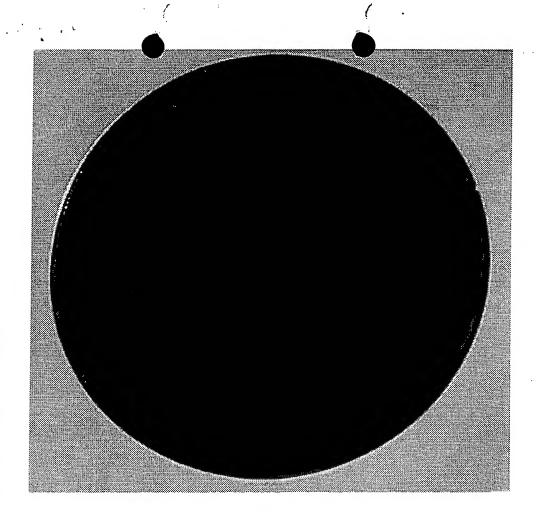
delamination

CSSIVIES CSEVEL









F19.4

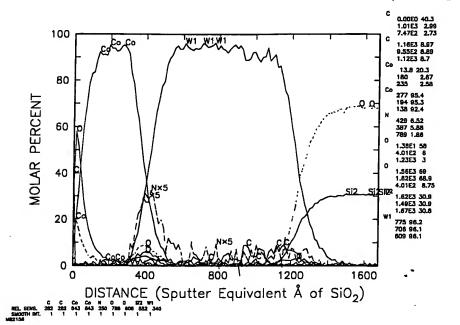


Fig. 5